

# ABSTRACT

Resist compositions comprising as the base resin a  
5 polymer using an alkoxyalkyl (meth)acrylate as a reactive  
group which is decomposable under the action of an acid to  
increase solubility in alkali have advantages including a  
practical level of shelf stability, a significantly enhanced  
contrast of alkali dissolution rate before and after  
10 exposure, a high sensitivity, and a high resolution over a  
wide baking temperature range. The compositions are best  
suited as a chemically amplified positive resist material for  
micropatterning in the manufacture of VLSI.